Electronic Supplementary Material (ESI) for Nanoscale Advances. This journal is © The Royal Society of Chemistry 2023

1	Supporting Information
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4	Spectrally selective microbolometer based on planar subwavelength
5	thin films
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23 **Table S1:** Calculated and measured resistance of the fabricated microbolometers.

Bolometers	$\boldsymbol{\rho}_{Au} \ (\boldsymbol{\Omega} \cdot \boldsymbol{cm})^1$	Cal. Resistance (Ω)	Exp. Resistance (Ω)
bare Au-200		115	115
bare Au-500	3×10^{-6}	110	120
bare Au-800		135	146
MIM-200	top: 8×10^{-6}	102	104
MIM-500	bottom: 3×10^{-6}	98	104
MIM-800	(Parallel Connection)	120	134

The calculated resistance (*R*) is obtained by using $R = \rho \cdot l/s$, where ρ , *l*, *s* are the electrical resistivity, length, and cross-sectional area of the resistor, respectively.

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Figure S1: Photographs and microscope images of the fabricated two types
microbolometers with various efficient areas, scale bars are 200µm.





40 Figure S2: Experimental measured absorption spectra of the MIM microbolometers

- 41 with three area size.



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Figure S3: The experimentally measured the resistance change of the fabricated microbolometer (magenta dotted line) under 0.2 mA and corresponding calculated $\ln(R/R_0)$ (blue dotted line). R_0 is the resistance of the device at temperature of 273 K, and the fitted TCR is 0.0014 K⁻¹.

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Figure S4: The experimentally measured responsivities of microbolometers with efficient area size of $500 \times 500 \ \mu\text{m}^2$, and $800 \times 800 \ \mu\text{m}^2$, as a function of modulation frequency.

61 Note 1: Calculation of the thermal conductance

The thermal conductance G can be theoretically calculated by²

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 $G = k \cdot S/h \tag{S1}$

64 Where k, S and h are the thermal conductivity of material, the contact area, and the 65 heat transfer distance, respectively.

Firstly, 2D heat distributions were calculated based finite element methods. In the 66 simulations, we replace the winding structure as planar thin films for both MIM and 67 68 bare Au devices to simplify the calculation, the sizes and thicknesses for each film are as the real devices. The planar thin film structures serve as the heat source on a quartz 69 substrate. The heat conductivities of gold, alumina, and quartz were taken from 70 literature². The thermal power density of the heat source of MIM structures is set one 71 order of magnitude larger than that of the bare Au control samples. After getting heat 72 distribution of each device at the response time, we then utilize the lateral heat 73 transfer distance d and vertical heat transfer distance t obtained from the simulated 74 results to calculate the contact area $(S=d^2)$ and distance (h=t). Finally, the effective 75 thermal conductance G, and the ratio of the absorption coefficient at 638 nm to the 76 effective thermal conductance (η/G) for each microbolometer can be calculated using 77 Eq. (S1). The calculated results are listed in Table S2. 78

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Table S2: Calculated G and η/G of the fabricated microbolometers.

Bolometers	τ (ms)	S (m ²)	h (m)	G(W/K)	η/G
bare Au-200	4.29	2.03×10 ⁻⁷	1.50×10 ⁻⁴	1.86×10 ⁻³	47.28
bare Au-500	6.60	5.63×10 ⁻⁷	1.50×10 ⁻⁴	5.18×10 ⁻³	17.02
bare Au-800	6.90	1.21×10 ⁻⁶	2.00×10 ⁻⁴	8.35×10 ⁻³	10.55
MIM-200	2.14	1.60×10 ⁻⁷	1.20×10 ⁻⁴	1.84×10 ⁻³	413.19
MIM-500	4.50	5.93×10 ⁻⁷	1.50×10 ⁻⁴	5.45×10 ⁻³	139.38
MIM-800	4.85	1.44×10 ⁻⁶	1.50×10 ⁻⁴	1.32×10 ⁻²	57.39

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